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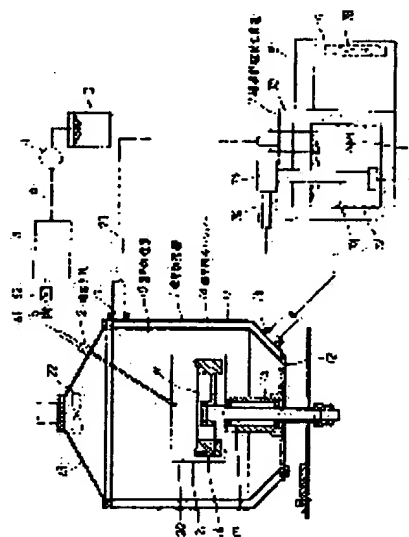
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(54) RESIST COATER

(57)Abstract:

PURPOSE: To control the environmental temperature of an object to be coated in a coating chamber with a high accuracy and cope with requirements of microtechnology and improve the product yield by circulating a constant temperature heat medium generated in a constant temperature heat medium generator in a heat exchange chamber surrounding the coating chamber.

CONSTITUTION: When the surface of a wafer W is coated with resist solution to form a resist layer, a constant temperature heat medium generator 7 is operated first and the temperature of constant temperature heat medium which is circulated in a constant temperature chamber 70 and a heat exchange chamber 14 is controlled at a preset temperature. After the temperature of the constant temperature heat medium which is circulated in the generator 7 and the heat exchange chamber 14 reaches the preset temperature, the resist solution is discharged from a nozzle 2 and dropped onto the surface of the wafer W and then the resist is spread on the surface of the wafer W by driving a rotary shaft 17 to rotate a spinning chuck 16 and, further, by increasing the revolution, the surface of the wafer W is coated with the resist uniformly. With this constitution, the requirements of microtechnology can be coped with and the product yield can be improved sufficiently.



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